

(w/English Abstract)

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			τ	S. PATENT	DOCUMENTS				
EXAMINER'S INITIALS	NO.	Document Number Number-Kind Codes (Manoum)		Publication Date MM-DD-YYYY	Name of Patentee or Appli Document		Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
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EXAMINER'S INITIALS	CITE NO.		reign Patent Document ntry Codes -Number 4-Kind Codes (# known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear		Translation Yes No	
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, **EXAMINER'S** journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where INITIALS CITE NO. United States Office Action Issued In United States Patent Application No. US 10/591,456, mailed /B.E./ January 29, 2009. European Search Report issued in European Patent Application No. EP 04818870.0, mailed March 12, /B.E./ 2009. MAJAMAA, T., et al., "Effect of Oxidation Temperature on the Electrical Characteristics of Ultrathin /B.E./ Silicon Dioxide Layers Plasma Oxidized in Ultrahigh Vacuum", Physics Scripta, 1999, Pages 259-262, Vol. T79 ROSS, E.C., et al., "Effects of Silicon Nitride Growth Temperature on Charge Storage in the MNOS /B.E./ Structure", Applied Physics Letters, December 15, 1969, Pages 408-409, Volume 15 Number 12 EXAMINER DATE CONSIDERED

/Brian Ensey/

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